

Appl. No. : 10/672,469
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IN THE ABSTRACT:

Please amend the abstract of the disclosure as follows:

An electron beam exposure apparatus for exposing a wafer by an electron beam, ~~including~~ incorporates a circuit structure for conducting a scan test to self-diagnose the electrical connections. The electron beam exposure apparatus includes: an electron beam generating section for generating the electron beam; a deflector for deflecting the electron beam; a deflection control section for outputting a deflection control signal for causing the deflector to deflect the electron beam; and a control signal storage section for storing a value of the deflection control signal output from the deflection control section. The control signal storage section and the deflector may be monolithically integrated on a semiconductor substrate.